

*B4*  
They are disposed on the gate insulating layer over the gate electrode 111, as shown in Figs. 7 and 8b.

Please replace the paragraph beginning at page 11, line 6, with the following rewritten paragraph:

*B5*  
On the passivation layer 137, a transparent conductive material such as ITO (Indium Tin Oxide) is deposited and patterned using a fifth mask process to preferably form a pixel electrode 141, a gate pad terminal 157 and a source pad terminal 167. The pixel electrode 141 connects to the drain electrode 131 through the drain contact hole 171. The gate pad terminal 157 connects to the gate pad 115 through the gate contact hole 151. The source pad terminal 167 connects to the source pad 125 through the source contact hole 161, as shown in Figs. 7 and 8e.

### In the Claims

Please amend claim 12 as follows (A marked-up version of the amended claim is attached):

12. (Amended) A method for manufacturing an active panel of a liquid crystal display device, comprising steps of:

providing a transparent substrate;

*B6*  
fabricating a plurality of gate and source lines above the transparent substrate, each line having a pad;

forming a first layer above the transparent substrate to cover at least a portion of the transparent substrate, wherein the first layer exposes the pad of the each line and defines at least one opening near the pad, the opening having a depth lower than the surface of the first layer; and

forming a second layer having a first part and a second part, wherein the first part is affixed to the pad to provide an electrical signal to the line and the second part is affixed to a bottom surface of the opening defined in the first layer to enhance adhesion between the first and second layers.